Attorney Docket # 10961260-2

CLAIM REJECTIONS - 35 U.S.C. §102(b)

Claims 1,2 and 4-6 have been rejected under 35 U.S.C. 102(b) as being anticipated by Kawakita.

Deep region oxides that were separated from each other were a problem in prior art (column 4, lines 4-5). This was a problem solved by the Kawakita isolation structure (column 4, lines 15-16). Kawakita teaches connecting <u>multiple</u> deep region oxides into a single continuous layer (column 3, lines 61-63), and specifically teaches away from non-continuous deep regions of oxide. The deep region oxides in Kawakita abut <u>multiple</u> shallow regions, the substrate, and <u>multiple other</u> deep regions.

In distinct contrast to the prior art, the deep region oxide of the present invention is not in contact with other deep regions, so the deep region abuts only a shallow region and the substrate (Figure 3). Furthermore, the present invention teaches a <u>single</u> deep region abutting only a <u>single</u> shallow region. These novel features specifically go against the teachings of Kawakita, and can be found in claims 1 and 5, which now recite a single deep region "abutting only substrate and a single shallow region". Claims 1 and 5 are believed to be allowable based on the novel feature cited within. Applicants respectfully submit that claims 1 and 5 are patentably distinct over the prior art.

Dependent claims 2 and 4 are believed to be allowable based on the allowability of claim 1. Dependent claim 6 is believed to be allowable based on the allowability of claim 5.

In summary, the claims are distinct and patentable over Kawakita, due to the above-mentioned novel features. The rejections under 35 U.S.C. §102(b) are believed to be overcome. Applicants respectfully request that the rejection be reconsidered and withdrawn.

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CONCLUSION

If the Examiner has any further questions or would like to discuss this application in more detail, he is invited to call the Applicants' agent at the telephone number given below. The Applicants respectfully suggest that the claims presently in the application are distinct over the prior art and that the application is now in condition for allowance. Accordingly, the Applicants solicit favorable action.

Respectfully submitted,

Min Cao, et al.

Judy L. Shie

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Agilent Technologies
Intellectual Properties Administration
Legal Department, M/S DL-429
815 SW 14th Street
Loveland, CO 80537
(408) 345-8920